

K-PRO series – run sheet

KemLab, Inc.

nanyte.com/photoresists/k-pro · last updated 2026-08-04

Thickness: 1–25 μm

Softbake: 115 °C · 2–5 min · hotplate

Exposure dose – dose by film thickness

Film thickness	Dose
1 μm	65 mJ/cm ²
2 μm	72 mJ/cm ²
3 μm	76 mJ/cm ²
4 μm	80 mJ/cm ²
7 μm	125 mJ/cm ²
15 μm	210 mJ/cm ²
25 μm	380 mJ/cm ²

Develop: Developer 0.26N TMAH